

L Number	Hits	Search Text	DB	Time stamp
1	2	jp-2000035665-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/09 08:57
-	2	((("20020068237") or ("20020068236")).PN.	US-PGPUB	2003/07/09 08:57
-	1975440	resin resist photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	16077	(photoacid acid) near generat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	78586	photosensitizer sensitizer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:05
-	1008314	solvent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/03 13:46
-	1234	(resin resist photoresist) and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer ) and solvent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/03 13:49
-	5890	benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	25	((resin resist photoresist) and ((photoacid acid) near generat\$3) and (photosensitizer sensitizer ) and solvent) and benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 11:40
-	155	IMAI-G IMAI-GENICHI IMAI-GENJI	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 16:22
-	6	(IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:01
-	78586	photosensitizer sensitizer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	5890	benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	61	(photosensitizer sensitizer ) same benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:08
-	16077	(photoacid acid) near generat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:04
-	1975440	resin resist photoresist	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:06
-	7	((photosensitizer sensitizer ) same benzopyran ) and ((photoacid acid) near generat\$3 ) and (resin resist photoresist )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:07
-	3	((photosensitizer sensitizer ) same benzopyran ) and ((photoacid acid) near generat\$3 ) and (resin resist photoresist ) not ((IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:07

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-	20	((photosensitizer sensitizer ) same benzopyran ) and (resin resist photoresist )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:08
-	13	((((photosensitizer sensitizer ) same benzopyran ) and (resin resist photoresist )) not (((IMAI-G IMAI-GENICHI IMAI-GENJI) and benzopyran) (((photosensitizer sensitizer ) same benzopyran ) and ((photoacid acid) near generat\$3 ) and (resin resist photoresist )))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:10
-	0	jp-8334897-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:10
-	2	jp-08334897-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:26
-	2	jp-11212252-\$.did. or jp-2000275823 or jp-2000056450	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:27
-	6	(jp-11212252-\$.did. or jp-2000275823 or jp-2000056450) jp-09138502-\$.did. jp-2000035665-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:27
-	2	jp-2000035665-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 12:49
-	2	titanocene same (\$\$acid near generator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 13:47
-	1	(titanocene adj compound) same (\$\$acid near generator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 13:47
-	0	((titanocene adj compound) same (\$\$acid near generator)) not (titanocene same (\$\$acid near generator))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 13:48
-	51	(radical adj generator) same ((acid photoacid) near generator)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:24
-	900	(resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:03
-	509	((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:26
-	3797882	photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:27
-	509	((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and (photocurable curable cur\$5 negative crosslinkable crosslinked crosslink (cross adj link\$4) cross-link\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:28
-	4167371	dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:30

-	4553605	coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:31
-	1655136	irradiate irradiating expose exposure exposing exposed irradiated irradiation	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:31
-	1640490	develop development developing developed )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:32
-	360309	(visible adj light) "VIS"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:32
-	57817	(dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation ) and (develop development developing developed )) and ((visible adj light) "VIS")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:33
-	208	((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation ) and (develop development developing developed )) and ((visible adj light) "VIS"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:37
-	50	((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation ) and (develop development developing developed )) and ((visible adj light) "VIS")) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 14:41
-	27	((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation ) and (develop development developing developed )) and ((visible adj light) "VIS")) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart) )	USPAT; EPO; JPO; DERWENT	2003/07/07 15:48
-	2	("6033826").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 15:48
-	1	((("6033826").PN.) and (generator) and (\$sensitizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 16:31

-	32	pyrene same (benzopyran)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 15:54
-	18	(((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation ) and (develop development developing developed ) and ((visible adj light) "VIS")))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart) ) ) and ((visible VIS) near light)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:03
-	0	(((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation ) and (develop development developing developed ) and ((visible adj light) "VIS")))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart) ) ) and ((visible VIS) near light)) and benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:02
-	0	(((((resin resist photoresist binder) and ((photoacid acid) near generator) and (photosensitizer sensitizer)) and negative) and ((dry drying heat-treat\$5 (heat\$5) bak\$4 pre-bake\$4) and (coat coating apply applying applied coated spin-coated spin-coat (spin adj (coated coat coating))) and (irradiate irradiating expose exposure exposing exposed irradiated irradiation ) and (develop development developing developed ) and ((visible adj light) "VIS")))) and (peel peeling peelable peeled (peel\$4-apart) (peel\$4 near apart) ) ) and benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:02
-	2248	((visible adj light) "VIS") and benzopyran	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:02
-	395	((visible adj light) "VIS") and benzopyran) and ((visible VIS) near light)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:03
-	293	(resin resist photoresist binder) and (((visible adj light) "VIS") and benzopyran) and ((visible VIS) near light))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:03
-	21	((photoacid acid) near generat\$3 ) and ((resin resist photoresist binder) and (((visible adj light) "VIS") and benzopyran) and ((visible VIS) near light)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 17:45
-	1	ls-148	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 18:04
-	2	JP-11258798-\$.DID.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/07 18:04

-	2	benzopyran adj condensed adj ring	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 11:34
-	7521	condensed adj ring	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 11:53
-	72	proliferating adj agent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 13:48
-	2661	sodium adj lamp	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 12:09
-	120	(sodium adj lamp) same (nm wavelength)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 12:10
-	72	proliferating adj agent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:31
-	2	jip-09138502-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 13:50
-	2	("6140025").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:06
-	12	(proliferating adj agent ) and (resin resist photoresist)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:09
-	0	(proliferating adj agent) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:35
-	134	(organic adj acid adj ester) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:58
-	83	((organic adj acid adj ester) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)) and (resist photoresist resin)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:58
-	79	((organic adj acid adj ester) same ((fluidity adj adjuster) (adhesion adj improver) (cissing adj inhibitor) (polymerization adj inhibitor) pigment plasticizer)) and (resist photoresist resin)	USPAT; EPO; JPO; DERWENT	2003/07/08 14:46
-	2648	(organic adj acid adj ester)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:58
-	1070	((organic adj acid adj ester) ) and (resist photoresist resin)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 14:59
-	834	((organic adj acid adj ester) ) and (resist photoresist resin)	USPAT	2003/07/08 15:13
-	0	430.270.1.ccls.	USPAT	2003/07/08 15:00
-	2718	430/270.1.ccls.	USPAT	2003/07/08 15:09
-	5	430/270.1.ccls. and ((organic adj acid adj ester) ) and (resist photoresist resin))	USPAT	2003/07/08 15:01
-	6	430/270.1.ccls. and ((organic adj acid adj ester) )	USPAT	2003/07/08 15:08

-	1	(430/270.1.ccls. and ((organic adj acid adj ester) )) not (430/270.1.ccls. and ((organic adj acid adj ester) ) and (resist photoresist resin))	USPAT	2003/07/08 15:08
-	112	430/\$.ccls. and ((organic adj acid adj ester) )	USPAT	2003/07/08 15:11
-	5270	430/\$.ccls. and (organic adj acid)	USPAT	2003/07/08 15:12
-	280	430/270.1.ccls. and (organic adj acid)	USPAT	2003/07/08 15:12
-	269	(430/270.1.ccls. and (organic adj acid)) and (resist photoresist resin)	USPAT	2003/07/08 15:23
-	89	((430/270.1.ccls. and (organic adj acid)) and (resist photoresist resin)) and (visible near light)	USPAT	2003/07/08 15:30
-	44	((430/270.1.ccls. and (organic adj acid)) and (resist photoresist resin)) and (visible near light)) and negative	USPAT	2003/07/08 16:20
-	97	positive and ((photoacid acid) near generator) and (photosensitizer sensitizer) and (visible near light)	USPAT	2003/07/08 16:21
-	155	IMAI-G IMAI-GENICHI IMAI-GENJI	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 16:22
-	2	(positive and ((photoacid acid) near generator) and (photosensitizer sensitizer) and (visible near light)) and (IMAI-G IMAI-GENICHI IMAI-GENJI )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 16:33
-	2	("5801212").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/07/08 16:33